Sviluppo di un fotomoltiplicatore a valanga basato su giunzione nanotubi di carbonio/Si

SCAPho-Silicon Carbon Avalance Photodetector

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Collaborations

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Photodetectors

p-n semiconducting or metal Schottky junction



1-Low-cost Rapid Room-temperature process Versatile deposition method Scalable tecnique Highly reproducible SWCNT random networks

Aqueous suspension of SWCNTS and anionic surfactant (SDS)

- Well dispersed suspension (ultrasonication and ultracentrifugation)
- Vacuum filtration process on cellulose filter
- Dry-transfer printing deposition method





Realization and properties of CNT films



metallic Non metallic



2- SWCNT thin films are conductive and semitransparent

Optical transmittance and electrical conductivity are two competing parameters both depending on the film thickness and the metallic CNT concentration



The SWCNT/n-Si device



Two possible configurations for two and three teminal measurements





$$\mathfrak{D} = \sqrt{\frac{A}{2eI_0}} \mathfrak{R}$$

The Detectivity measures the ability of a PD to detect small signals



Three terminals vs. two terminals configuration using Pulsed laser 40 fs, 31 pJ-1µJ



Our photodetector vs. not polarized commercial APD

	Active	Responsivity	Breakdown	Dark	Capacitance	Rise	Spectral	Gain
	area		voltage	current		time	range	
								$V > V_B$
								D
Hamamatsu	0.8 mm ²	0.5 A/W	200 V	0.5 nA	5 pF	1.5 ns	300 nm-	105
Si APD							1000 nm	
S12053								
Osi	0.2 mm ²	0.45 A/W	15 V	0.06 nA	1.8 pF	0.8 ns	400 nm-	
Optoelectronics							1000 nm	
HR020 series								
Our SWCNT/Si	9 mm²	1.2 A/W	20 V	<1 nA	5 nF	3-5 ns	300 nm-	Not
detectors							1000 nm	meas.

SWCNT junctions as candidates for Avalance PhotoDetectors (APD) and possibly for Multi Pixel Photo Counters (MPPC) for single photon detection



An APD works at a reverse voltage just above the break down. The photon absorption cause a huge increase of the reverse current

Improvement in the breakdown region is strongly demanded



Hamamatsu APD



New designed FBK substrates to improve the junction quality through a better contact of the SWCNT film with the Si substrate



Parameters of interest:

In dark conditions Voltage breakdown (~30 V), dark current (<1 nA), reverse voltage characteristics as a function of temperature and magnetic field. Schottky or p-n junction

Under light Quantum efficiency, responsivity, detectivity, response time, gain and their dependence on the temperature

SCAPho Silicon Carbon Avalance Photodetector

2 years.

Available facilities

INFN Roma2

-SWCNT film fabrication facilities

-Monocromator

-Lamp

-Current/voltage power supply

-Visible wavelengths Femtosecond laser

source

INFN Salerno

-Low temperature transport measurement facilities

-Cryostat with 9 T superconducting magnet

Workplan and financial support required

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Description	Final date of the action	Equipment	Costs (euro)
New FBK substrates.Electrical and magneticcharacterization of the SWCNT thin films.SWCNT film deposition on FBK substrates; junctioncharacterization vs. temperature.Arrangement of existent	30-06-2019 31-12-2019	Picoammeter; FBK substrates; chemicals Optical fibers,	30000
facility for electrooptical measurements at different temperature.		adaptors, cryogenic supplies	
Electro-optical measurements under light. Quantum efficiency, responsivity, detectivity vs. Temperature. Time response measurements. Optimization of the fabrication parameters.	30-06-2020	Refrigeration liquids, cryogenic feedthrought, mirrors, filters, optical spares	15000
APD electrical circuit; avalance photodetector response; gain measurement vs. light power, temperature, wavelength.	31-12-2020	Electronics, refrigeration liquids.	